In the Claims:

Please amend Claim 1 as indicated below. The status of all claims is as follows:

1. (Original) A method of manufacturing a substrate for a liquid-crystal display device comprising the steps of:

forming a resin layer on a substrate;

selectively reforming the surface portion of said resin layer by applying energy with an energy density per unit time of a prescribed value or more to said resin layer to generate a difference in a rate of thermal shrinkage between said surface portion and the layer portion other than the surface portion in said resin layer;

performing a heat treatment to said resin layer to form undulations in said surface portion; and

forming reflective electrodes on said surface portion.

2. (Original) The method of manufacturing a substrate for a liquid-crystal display device according to claim 1,

wherein said energy is applied by irradiation with light.

3. (Original) The method of manufacturing a substrate for a liquid-crystal display device according to claim 2,

wherein said energy is applied by irradiation with ultraviolet rays.

4. (Original) The method of manufacturing a substrate for a liquid-crystal display device according to claim 3,

wherein said energy is applied by irradiation with said ultraviolet rays with an illuminance exceeding 12 mW/cm^2.

5. (Original) The method of manufacturing a substrate for a liquid-crystal display device according to claim 3,

wherein said energy is applied by irradiation with said ultraviolet rays with an illuminance of no more than 12 mW/cm^2 and said resin layer is in a semi-hardened condition prior to the application of said energy.

6. (Original) The method of manufacturing a substrate for a liquid-crystal display device according to claim 5,

wherein heat treatment of said resin layer is performed at a prescribed temperature prior to the application of said energy.

7. (Original) The method of manufacturing a substrate for a liquid-crystal display device according to any of claims 1 to 6,

wherein photosensitive resin is employed for said resin layer.

8. (Original) The method of manufacturing a substrate for a liquid-crystal display device according to claim 7,

wherein novolac resist is employed for said resin layer.

9. (Currently Amended) A method of manufacturing a liquid-crystal display device in which a pair of substrates are manufactured and said substrates are mutually stuck together so that liquid-crystal is sealed between said substrates, wherein

one of said substrates is manufactured using a method of manufacturing a substrate for a liquid-crystal display device according to any of ~~claims 1 to 8.~~ claims 1 to 6.

10. (Original) A method of manufacturing a substrate for a liquid-crystal display device comprising the steps of:

coating a resin layer on a substrate, wherein the resin layer can be at least three conditions including a non-harden condition, a semi-harden condition and a harden condition through a heat treatment;

performing a first heat treatment to the resin layer to make the resin layer the harden condition or the semi-harden condition;

applying energy having a energy density per a unit time, which is more than a prescribed value, to the resin layer so as to selectively reform the surface portion of said resin layer and to generate a difference in a rate of thermal shrinkage between said surface portion and the layer portion other than the surface portion;

performing a second heat treatment to the resin layer to form undulations in said surface portion; and

forming a reflective electrode on said surface portion.

11. (Original) The method of manufacturing a substrate for a liquid-crystal display device according to the claim 10,

wherein, in said first heat treatment, the semi-harden condition is made by a first pre-bake treatment with from 80 to 130 degrees centigrade, the harden condition is made by the first pre-bake treatment and a second pre-bake treatment, and

the energy having a energy density per a unit time, which is more than a prescribed value, is given by an irradiation of ultra-violet light whose energy density per a unit time is more than 12 mW/cm^2.

12. (Original) A method of manufacturing a substrate for a liquid-crystal display device comprising the steps of:

coating a resin layer on a substrate, wherein the resin layer can be at least three conditions including a non-harden condition, a semi-harden condition and a harden condition through a heat treatment;

performing a first heat treatment to the resin layer to make the resin layer the semi-harden condition;

applying energy having a energy density per a unit time, which is no more than 12 mW/cm^2, to the resin layer so as to selectively reform the surface portion of said resin layer and to generate a difference in a rate of thermal shrinkage between said surface portion and the layer portion other than the surface portion;

performing a second heat treatment to the resin layer to form undulations in said surface portion; and

forming a reflective electrode on said surface portion.

13. Currently Amended) The method of manufacturing a substrate for a ~~liquid-~~ liquid-crystal display device according to the claim 12,

wherein, in said first heat treatment, the semi-harden condition is made by a first pre-bake treatment with from 80 to 130 degrees centigrade.